Applicants: Mamoru NAKASUJI, et al.

Serial No.: 09/891,611

Docket No.: 010817

Page 2

Û

75. (Amended) A method for manufacturing semiconductors by using the inspection apparatus of claim 71 or 72.

W COMPLETED TO THE PROPERTY OF THE PROPERTY OF

81. (Amended) A device manufacturing method for evaluating a wafer during manufacturing process by using the inspection apparatus of any one of claims 77 to 79.

Please add new claims 101-104 as follows:

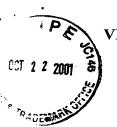
101. (New) A method for manufacturing semiconductor devices wherein a wafer during a manufacturing process or after processing is evaluated by using the inspection apparatus of claim 53.

15 W

102. (New) A method for manufacturing semiconductors by using the inspection apparatus of claim 73.

103. (New) A method for manufacturing semiconductors by using the inspection apparatus of claim 74.

104. (New) A device manufacturing method for evaluating a wafer during manufacturing process by using the inspection apparatus of claim 80.



VERSION WITH MARKINGS TO SHOW CHANGES MADE U.S. Serial No. 09/891,611

IN THE CLAIMS:

Claims 53, 55, 75 and 81 have been amended as follows:

- 53. (Amended) The inspection apparatus of claim-52 51 or 52 wherein the apparatus is constructed so that an energizing condition of an objective lens is obtained under a state where a pattern on a wafer is electrically charged.
- 55. (Amended) A method for manufacturing semiconductor devices wherein a wafer during a manufacturing process or after processing is evaluated by using the inspection apparatus of any one of claims 51-54 51, 52 or 54.
- 75. (Amended) A method for manufacturing semiconductors by using the inspection apparatus of any one of claims 71 to 74 claim 71 or 72.
- 81. (Amended) A device manufacturing method for evaluating a wafer during manufacturing process by using the inspection apparatus of any one of claims 77 to 80_79.